

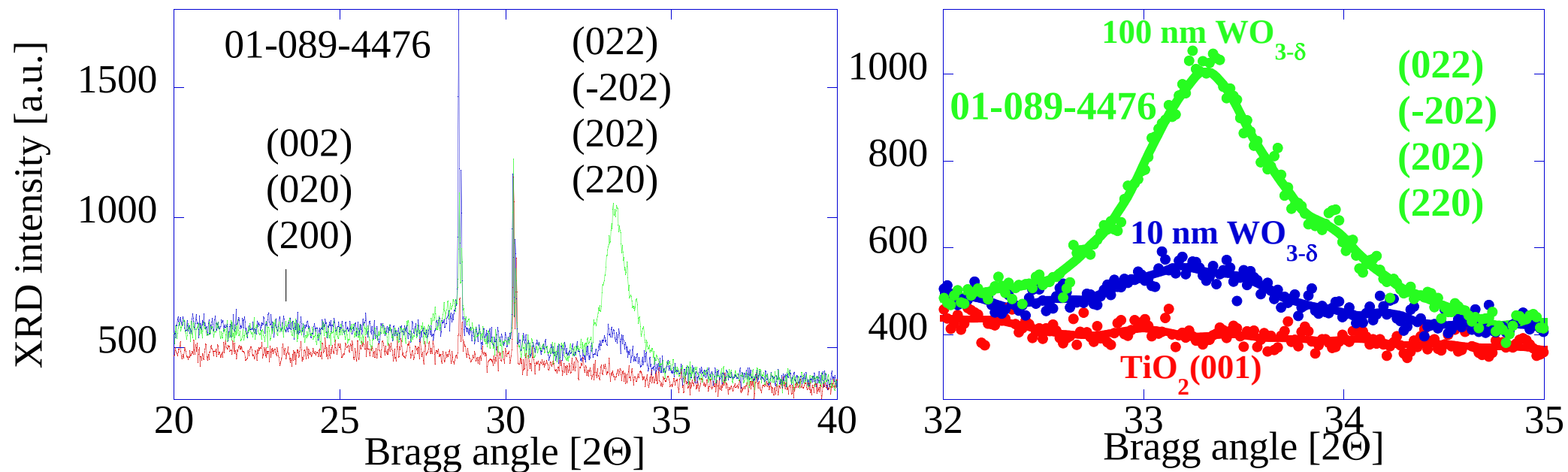


Figure S1: Comparison of X-ray diffractograms of clean TiO_2 substrate and 10 nm and 100 nm as-deposited films grown on the same (001) substrate. The film peaks at 33.4° are identified with (022) of WO_3 , see JCPDF reference card 01-089-4476.

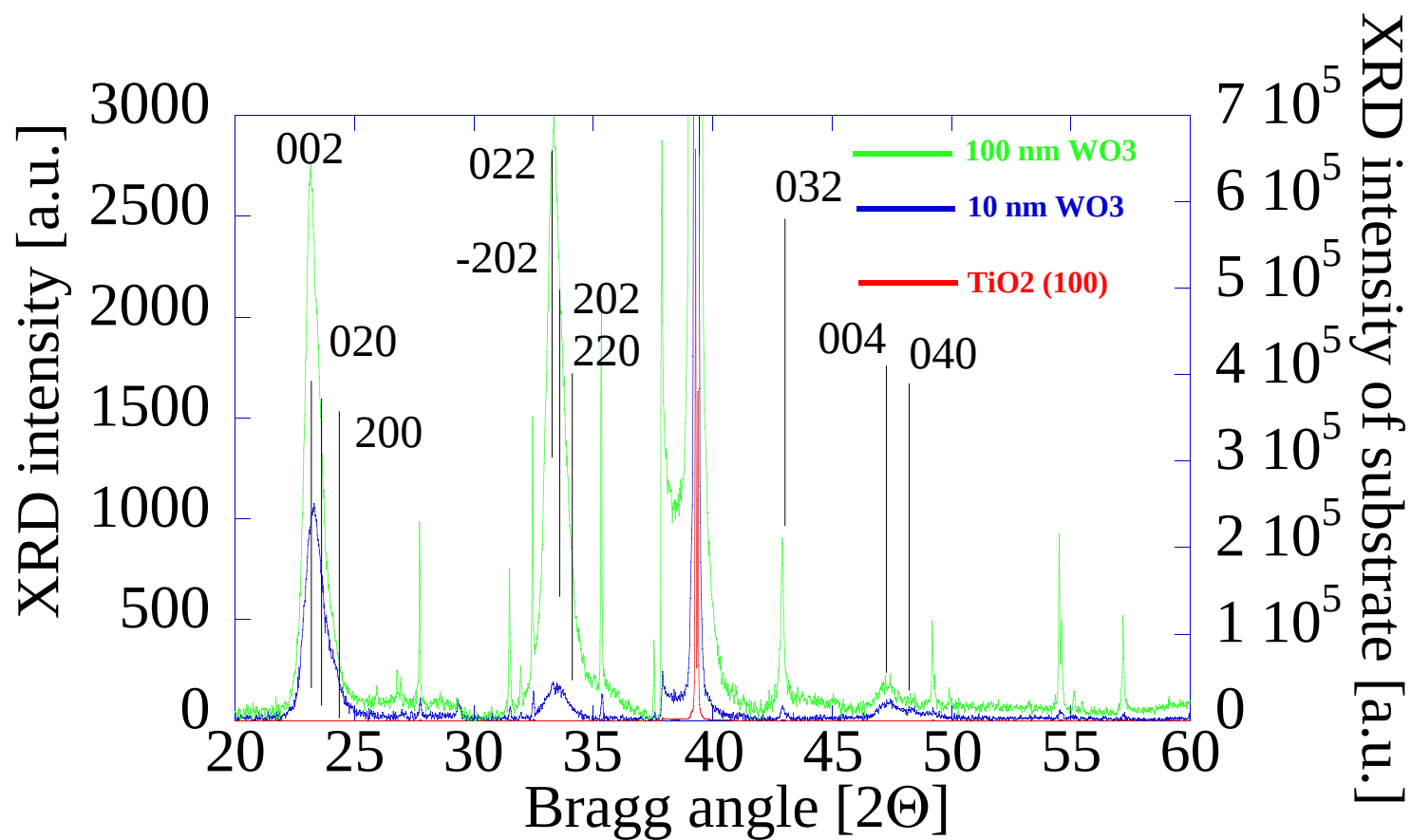


Figure S2: Comparison of X-ray diffractograms of TiO₂ substrate and 10 nm and 100 nm as-deposited films grown on the (100) substrate. The straight thin lines are taken from JCPDS reference card 43-1035.

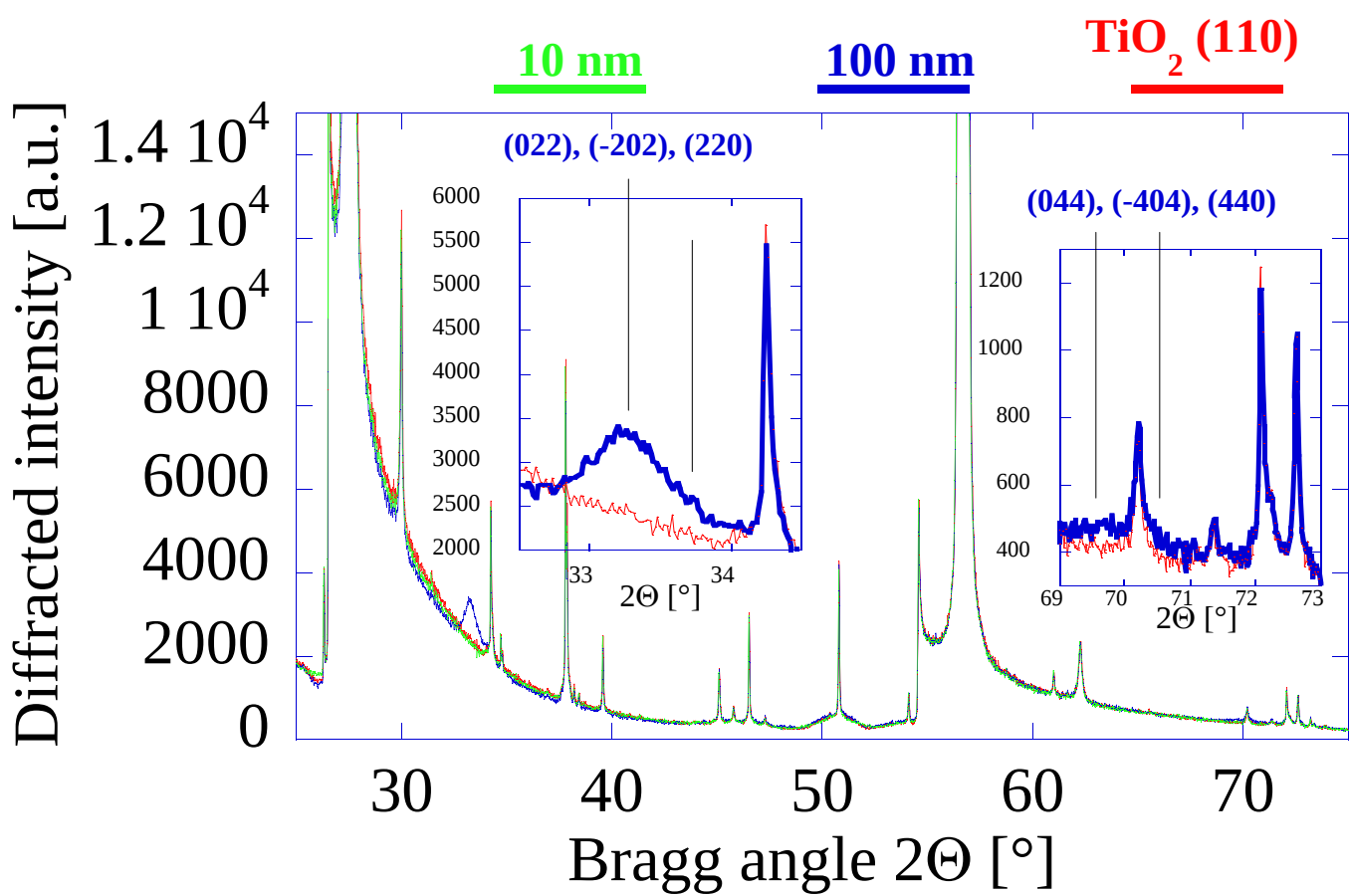


Figure S3: Comparison of X-ray diffractograms of TiO_2 substrate and 10 nm and 100 nm as-deposited films grown on the (110) substrate.